Admont



This project has received funding from the ECSEL Joint Undertaking under grant agreement No 661796. This Joint Undertaking receives support from the European Union's Horizon 2020 research and innovation programme and Germany, Finland, Sweden, Italy, Austria, Hungary."



ADMONT

ADMONT Essential Capabilities & Services X-FAB Dresden GmbH&Co.KG

> Information for potential ADMONT pilot line user V2.0 Status 07/2015

Advanced Distributed Pilot Line for More-than-Moore Technologies

Who is ADMONT?

Advanced Distributed Pilot Line for More-than-Moore Technologies

ADMONT is a **multi-KET pilot line** driven by a **combination** of **technology platforms** in Dresden carried by industry and research institutes serving pilot line clients in Europe

- ADMONT is organised along the **value chain** from wafer material, CMOS wafer, sensor and OLED processing to silicon system integration in one production flow
- ADMONT is an ECS (European Electronics Components and Systems) ecosystem in Saxony for Europe with sustainable impact on economic growth and employment in the European Union
- ADMONT addresses key applications: smart mobility, smart energy, smart health and smart production in excellent agreement with the ECSEL Multiannual Strategic Plan
- ADMONT addresses essential capabilities: **semiconductor process equipment** and **materials**, **design technology**, **smart system integration**

ADMONT as a distributed More-than-Moore pilot line is unique in Europe and worldwide.

Admont



Admont

ADMONT Concept & Capabilities

ADMONT pilot line concept, structure and excellences



Design: XFAB, PE, FhG-EAS, FhG-EMFT, FhG-FEP, IMMS, MAZeT, EDC

*1 Essential Capability Modul

Detailed Information are available under (Link: XFAB, IPMS, FEP, ASSID)

20 July, 2015



THE MORE THE MORE THAN MORE FOUNDRY.



INTRODUCTION X-FAB DRESDEN ADMONT CMOS-HV PILOT LINE





Presenter Rev.2 KHS 07/2015

20 July 2015





History, Location, Business Modell, Service Offering

History Dresden

1961 Founded* AMD

1999 Privatized, IDM-Model, 5 inch production line

2001 6 inch

- 2007 X-FAB, Foundry-Model
- 2009 8 inch
- 2011 50 years Microelectronic Dresden
- 2013 8 inch capacity extension

*1961- Professor Werner Hartmann founded , Arbeitstelle für Molekularelektronik Dresden'











Locations - Dresden



- **Processes** 0.35µm ultra-high-voltage CMOS process (XU035)
 - 0.35µm HV and analog/mixed-signal CMOS (XH035)
 - 0.35µ integrated Thermopile in CMOS XT-035
 - 0.6µm HV and analog/mixed-signal CMOS
 - special purpose customer specific 0.6 and 0.35µm analog/mixed-signal/HV CMOS processes

Overall capacity > 8,000 eight inch equivalent wafer starts per month

Wafer size	8"
Clean Room	ISO Class 3
Employees	~400 (+36), 25 R&D







X-FAB Dresden: Grenzstraße 28, 01109 Dresden



Business Model



- > X-FAB is a pure-play foundry provider
- Provides IC manufacturing solutions to fabless firms, IDMs & OEMs
- > Focus on More than Moore technologies
- > Foundry solutions:
 - Open platform technologies
 - Sensors, MEMS
 - Outsourcing / Custom process implementation



Service Offering



- > Comprehensive design support
 - Hotline service & 24/7 online access to full technical documentation
 - PDKs for all major EDA vendors
 - Optimized analog and digital libraries; statistical models; simulation
- > Flexible & low cost prototyping options
 - MPW & MLM service
- > Manufacturing excellence
 - High reliability (zero ppm support)
 - Process longevity to support long lifetime products
 - Full online reporting for efficient supply chain management
 - Second source capabilities for major technologies



Best-in-Class Design Support



- > Most comprehensive design support in foundry industry
- PDKs support 3 Sigma consumer applications; up to 6 Sigma for automotive applications in temperature range from -40°C up to 175°C
 - Support of all major EDA platforms (Cadence, Mentor, Synopsys, Tanner)
 - Digital libraries developed for dedicated mixed-signal needs (low power, low noise, junction isolated)
 - Model accuracy and design flow which support first time right for analog and mixed-signal designs
 - Design kit trainings, design reviews and ESD consultancy on request
- > Wide range of embedded non-volatile memory IP: eFlash, EEPROM, OTP
- > 24 hour Hotline service available









Essential Capabilities

Analog / High-Voltage

- > Best-in-class analog characterization & design support
- Covering voltages up to 40V, 60V, 100V, 200V & 700V for CMOS and SOI solutions
- Combination of high-voltage and NVM options with lowest mask count in industry for advanced analog/mixed-signal process nodes
 - NVM options include eFlash, EEPROM, OTP
- > Supported applications include:
 - Power management ICs
 - DC/DC converter
 - AC/DC
 - AC LED
 - Precision analog
 - White Light LED driver
 - BLDC controller







Automotive



- > Foundry offering meeting automotive requirements:
 - Reliability (0 ppm approach)
 - Robustness
 - High temperature / High voltage
 - Long product lifetime support
 - Production Part Approval Process (PPAP)
- > Quality systems:
 - ISO TS 16949 certification for all sites
 - Technologies qualified according to AEC-Q100
 - Audited and approved by major OEMs
- Process & design kit development and quality systems all are geared towards meeting or exceeding the stringent automotive standards
- > At X-FAB We think automotive.



Opto Sensors in CMOS

XFAB

- Providing technologies with integrated CMOS image sensors in XH035
- > Wide range of characterized photo diodes on multiple process platforms
 - High sensitivity
 - Adjustable spectral range
- Lowest 1/f noise level and excellent matching behavior for high-performance signal conditioning applications
- > Supported applications include:
 - Ambient light sensor
 - CMOS image sensors for industrial & medical applications
 - Microphone amplifier

0.35µm (XH035)



Sensor Interfaces fluidic Lab on Chip XFAB

OLED (or planar metal)-CMOS Interface and Target Specification



Parameter		Unit
Total step on top metal surface (edge height incl. oxide edge)	<65	nm
Surface roughness (RMS) within pixel area		nm
Surface roughness (Z-range) within pixel area, incl. Via dimple		nm
Max. protrusion height ("spikes") within pixel area		nm
Maximum depth of defects within pixel area		nm



> RMS<6nm: CMP, IMO-CVD, Etch, Metal-PVD</p>

OLED metal with Via dimple

Process Capabilities Overview



Performance & Commitment





ADMONT Grant Agreement No. 661796

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